

# Flexible functional oxides on muscovite via van der Waals epitaxy

Tahta Amrillah<sup>1</sup>, Chun-Hao Ma<sup>2</sup>, Ping-Chun Wu<sup>2</sup>, Ying-Hui Hsieh<sup>2</sup>, Ha Thai Duy<sup>1</sup>, Yi-Ying Chin<sup>3</sup>, Hong-Ji Lin<sup>3</sup>, Yi-Chun Chen<sup>4</sup>, Ying-Hao Chu<sup>1,2</sup>, **Jen-H-Yih Juang**<sup>1\*</sup>

<sup>1</sup>Department of Electrophysics, <sup>2</sup>Department of Materials Science and Engineering, National Chiao Tung University, Hsinchu 30010, Taiwan

<sup>3</sup>National Synchrotron Radiation Research Center, Hsinchu 30076, Taiwan

<sup>4</sup>Department of Physics, National Cheng Kung University, Tainan 70101, Taiwan

In this presentation, we will discuss some of our recent efforts in developing flexible functional oxides, which might of potential applications in spintronics and multiferroic composites. Four representative functional oxides, namely the highly conductive MoO<sub>2</sub> layers suitable for the base layer in forming heterostructure with other oxides, the fully spin polarized Fe<sub>3</sub>O<sub>4</sub>, magnetostrictive CoFe<sub>2</sub>O<sub>4</sub> (CFO) and multiferroic nanocomposite consisting of ferroelectric BiFeO<sub>3</sub> (BFO) and ferrimagnetic CoFe<sub>2</sub>O<sub>4</sub> (CFO), have been deposited on flexible muscovite (mica) substrates via van der Waals epitaxy using pulsed laser deposition technique. The quality of the films grown on mica has been carefully characterized using various analytical tools to demonstrate the viability of preserving their respective intrinsic properties using the present processes. Moreover, the mechanical stability and robustness were tested by cyclic bending test to over 1000 cycles to evaluate their potential usage in flexible oxide electronics.

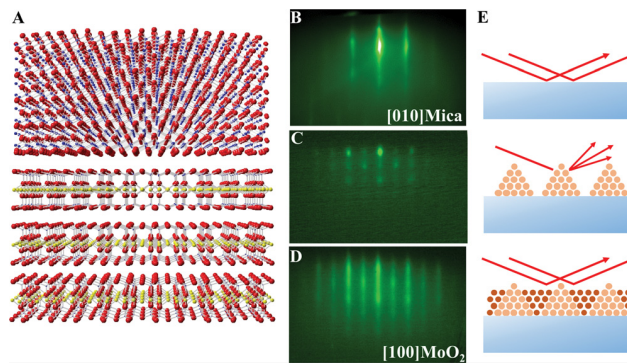


FIG. 1. (a) Schematic representation of van der Waals epitaxial MoO<sub>2</sub> (top, Mo in blue and O in red) on muscovite (bottom, Si in yellow and O in red). RHEED patterns recorded (b) before the deposition, (c) in the early stage of growth, and (d) after the deposition process. (e) Schematic of growth mechanism.

Ma et al., APL, 2016

\*Supported by MOST and MOE of Taiwan; e-mail: [jjjuang@cc.nctu.edu.tw](mailto:jjjuang@cc.nctu.edu.tw)

## References:

1. C. H. Ma, J. C. Lin, H. J. Liu, T. H. Do, Y. M. Zhu, T. H. Ha, Q. Zhan, J. Y. Juang, Q. He, E. Arenholz, P. W. Chiu\*, and Y. H. Chu\*, "Van der Waals epitaxy of functional MoO<sub>2</sub> film on mica for flexible electronics", *Appl. Phys. Lett.* **108**, 253104 (2016).
2. H. J. Liu, C. K. Wang, D. Su, T. Amrillah, Y. H. Hsieh, K. H. Wu, Y. C. Chen, **J. Y. Juang**, L. M. Eng, S. U. Jen\*, Y. H. Chu\*, "Flexible heteroepitaxy of CoFe<sub>2</sub>O<sub>4</sub>/Muscovite bimorph with large magnetostriction", *ACS Appl. Mater. Interfaces* **9**, 7297-7304 (2017).
3. T. Amrilla, Y. Bilita, K. Shin, T. Yang, Y. H. Hsieh, Y. Y. Chiou, H. J. Liu, Do Thi Hien, D. Su, Y. C. Chen, S. U. Jen, L. Q. Chen, K. H. Kim, and **J. Y. Juang\***, Y. H. Chu\*, "Flexible multiferroic bulk heterojunction with giant magnetoelectric coupling via the van der Waals epitaxy", *ACS Nano* **11**, 6122-6130 (2017).